

20. The composition of claim 19 which has a softening point of greater than 750°C.

21. The composition of claim 19 which has a thermal expansion coefficient α_{20-300} of between 60 and $88 \times 10^{-7} \text{°C}^{-1}$.

22. The composition of claim 19 which has a strain point of greater than 570°C.

23. The composition of claim 19 wherein the working point is less than 1190°C, the softening point is at least 805°C, the thermal expansion coefficient is between 75.6 and $86 \times 10^{-7} \text{°C}^{-1}$, and the strain point is between 580 and 590°C.

24. The composition of claim 19 wherein the ϕ coefficient satisfies the relationship

$$0.7 \text{MPa}^2 / \text{°C}^2 < \phi^2 \cdot c/a < 2 \text{MPa}^2 / \text{°C}^2$$

25. The composition of claim 19, comprising the following components:

SiO ₂	55-75%
Na ₂ O	5-10%
CaO	8-12%
Al ₂ O ₃	0-7%
ZrO ₂	0-8%
K ₂ O	0-8%

26. The composition of claim 19 comprising the following components:

SiO ₂	55-75%
Na ₂ O	2-8%
K ₂ O	2-8%
CaO	4-11%
Al ₂ O ₃	0-7%
ZrO ₂	0-8%
MgO	0-4%

27. The composition of claim 19 comprising the following components:

SiO ₂	55-75%
ZrO ₂	3-8%
Na ₂ O	4.5-8%
K ₂ O	3.5-7.5%
CaO	7-11%
Al ₂ O ₃	0-5%

28. The composition of claim 19, comprising the following components:

SiO ₂	64.5-75%
ZrO ₂	3-7.5%
Na ₂ O	5-9%
K ₂ O	3.5-7.5%
CaO	5-11%
SrO	3-9%
Al ₂ O ₃	0-1%
MgO	0-2%
BaO	0-1.5%

29. The composition of claim 19, wherein ϕ is between 0.75 and 0.84, and having a strain point of greater than 507°C and an electrical resistivity such that $\log \rho_{(250^\circ)}$ is greater than 6.6.

30. The composition of claim 29 wherein the strain point is between 530 and 590°C and the electrical resistivity is such that $\log \rho_{(250^\circ)}$ is greater than 8.

31. An article comprising the glass composition of claim 19.

32. The article of claim 31 in the form of a monolithic glazing panel, a plasma-screen substrate, an electroluminescent-screen substrate; an electroluminescent-screen substrate or a cold-cathode-screen substrate.